

# The Performance of Glass-GEM

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Zaragoza

- ▶ Background
  - GEM for sealed gas application
- ▶ Glass GEM
  - Fabrication process
  - Characteristics
- ▶ Experimental Results
  - Fe-55 Source
  - Synchrotron radiation
- ▶ Summary



The Glass GEM

*We fabricated a GEM with brand new material,*

**Photo Etchable Glass**

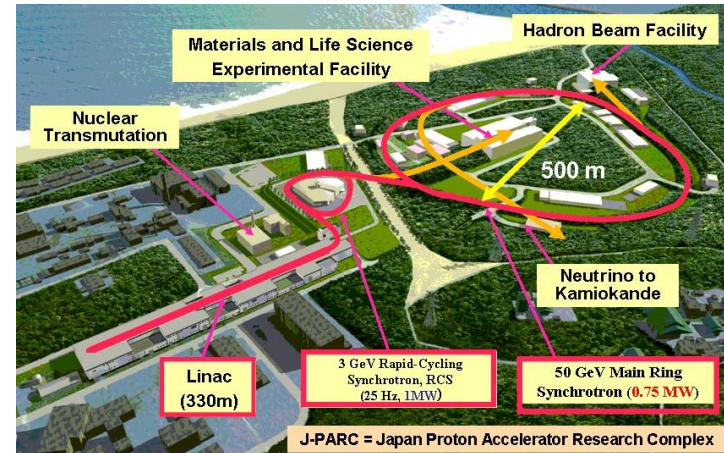
## ▶ TOF Neutron Detector

- ▶ For reflectometer
- ▶ High gain
- ▶ Stability
- ▶ Uniformity
- ▶ High count rate
- ▶ Hydrogen free material
- ▶ Sealed gas (He-3)

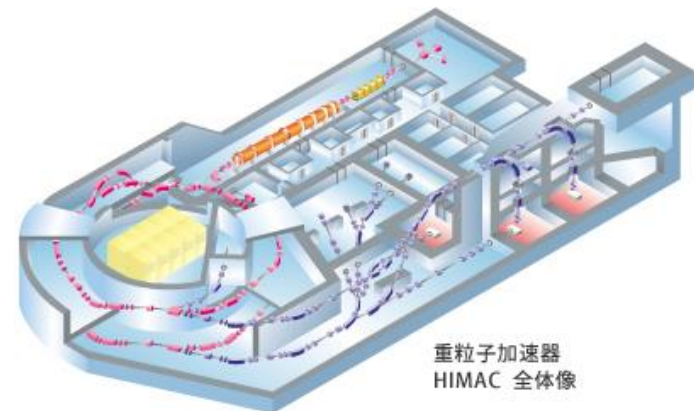
## ▶ Medical application

- ▶ 2-D dosimeter for Carbon beam (Cancer therapy)
- ▶ Sealed gas chamber (Hospital)

## Focusing on sealed gas application

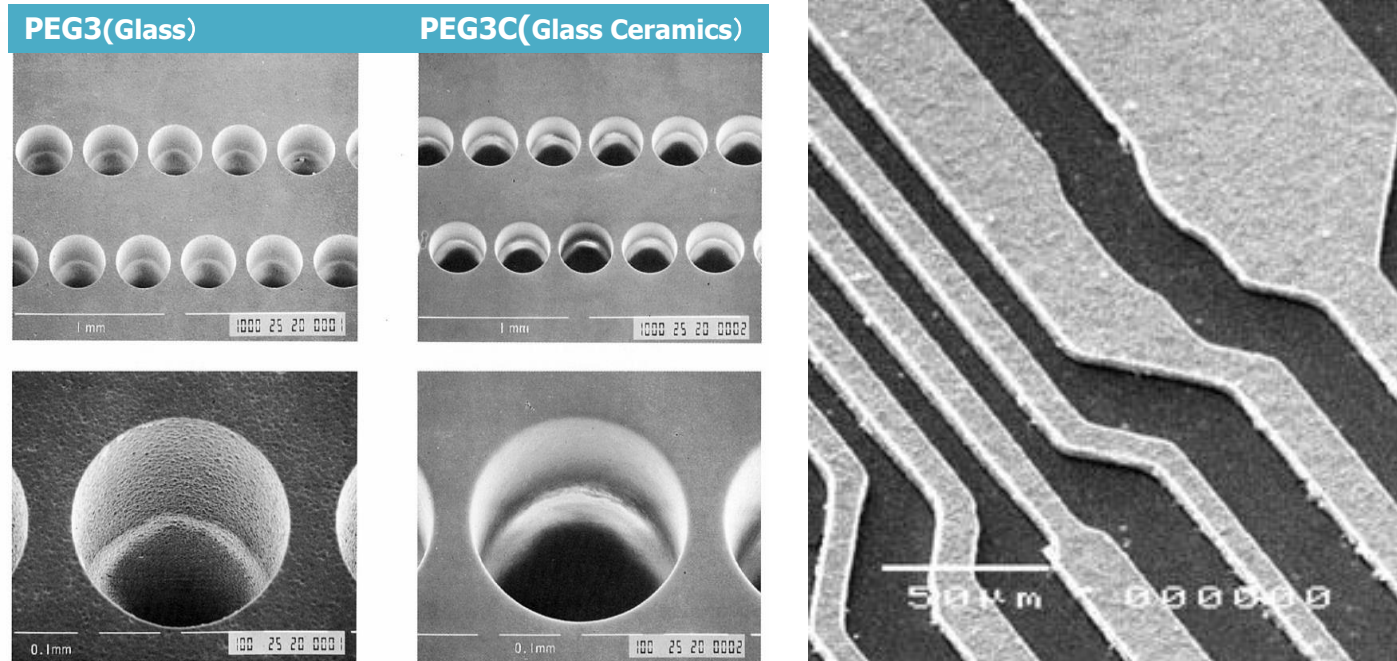


Neutron detector for J-PARC



HIMAC (Heavy-Ion Medical Accelerator in Chiba) Takeshi Fujiwara

## Photo Etchable Glass 3 : PEG3



### Features

- Via-Hole and Trench Structure
- High Aspect Ratio
- Small Diameter
- 3-Dimensional Fabrication Process
- Transmits Light (PEG3)
- Smooth and Flat Surface

### Application

- Glass Circuit Board
- Ink-Jet Print Head
- MEMS
- Flat Panel Display
- Optical Fiber Guide
- Wire Guide for IC Final Tester

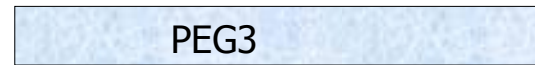
# Comparison PEG3 glass with Polyimide

ITEM	Units	PEG3	Polyimide
Thermal conductivity @25° C	W/m K	0.795	0.3
Young's modulus	GPa	79.7	18.6
Dielectric const. @1GHz		6.28	3.55
Volume resistivity@25° C	W cm	$8.5 \times 10^{12}$	$\sim 10^{18}$
Thickness	mm	0.1 - 1	
Min. Hole Diameter	$\mu\text{m}$	10	
Aspect ratio of Via Hole	Thickness/ Via Hole Diameter	30	

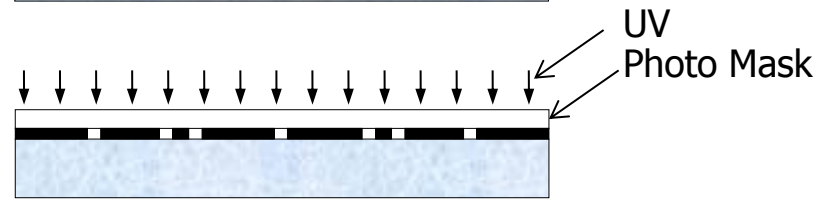


## Photo Etchable Glass 3 : PEG3

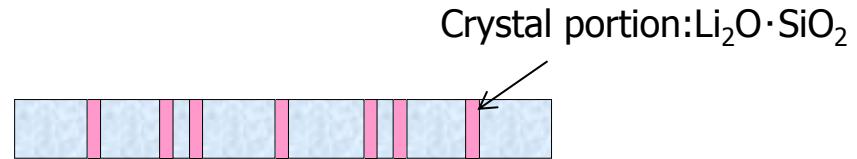
1. Glass Substrate



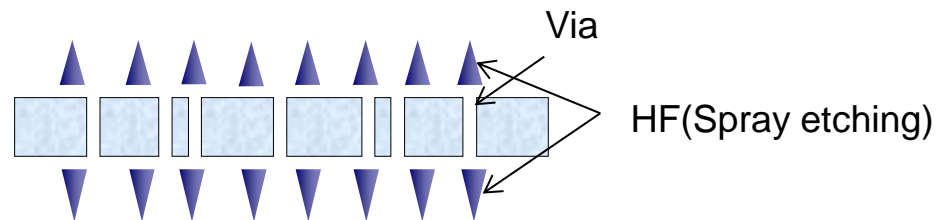
2. UV exposure (1<sup>st</sup>\_exp)



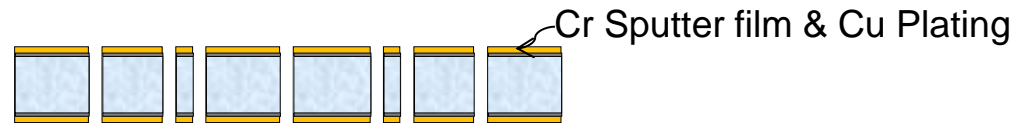
3. Crystal formation  
(1<sup>st</sup> heat treatment)



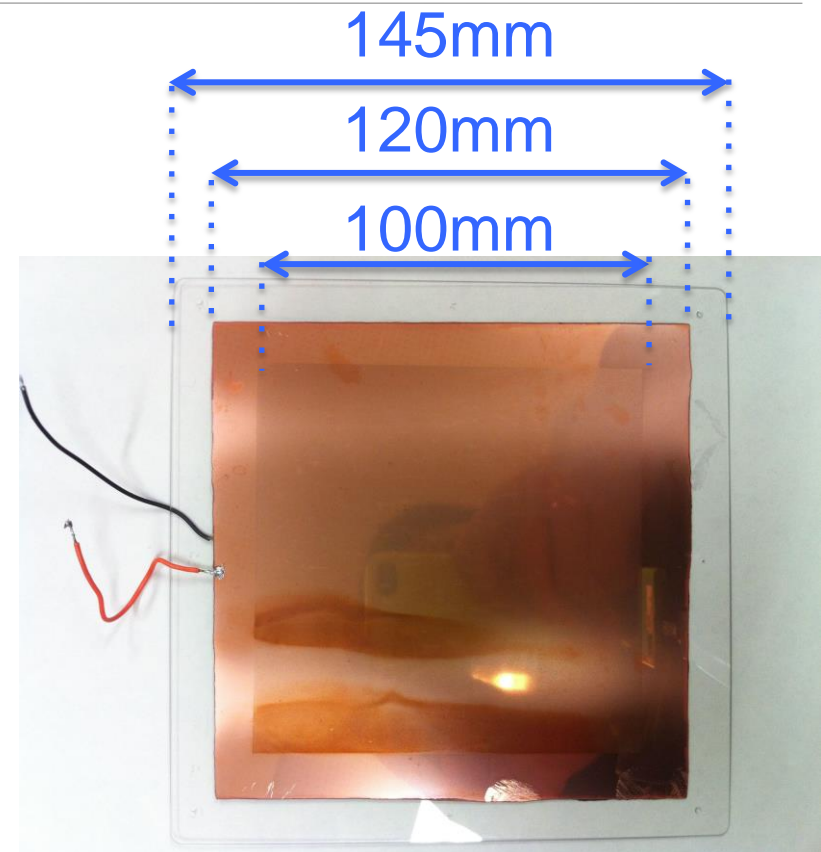
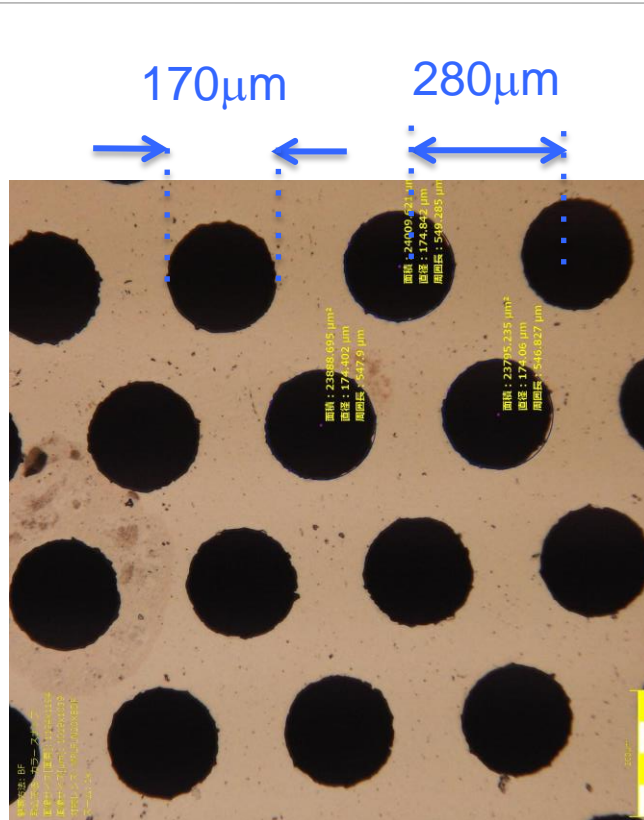
4. Via etching  
(hydrogen fluoride wet etch)



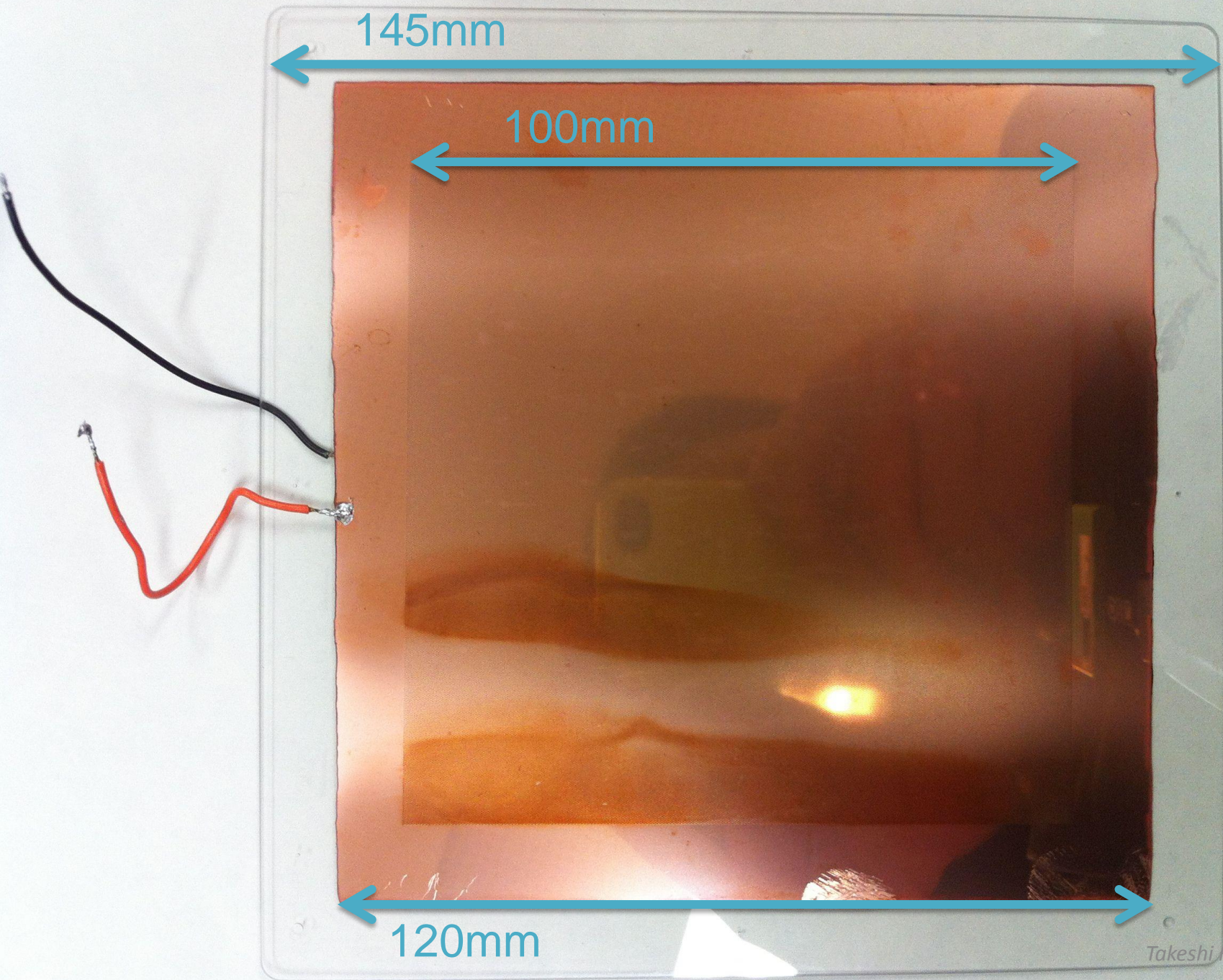
5. Cu/Cr Plating and Sputtering



## Photo Etchable Glass 3 : PEG3



- ▶ Substrate: 145 mm x 145 mm
- ▶ Effective area: 100 mm x 100mm
- ▶ Thickness: 680µm (410~800µm)
- ▶ Electrode: Cu + Cr
- ▶ Hole pitch: 280µm
- ▶ Hole dia.: 120~190µm



145mm

100mm

120mm



## Easy to handle

- ▶ Needs no support to mount a GlassGEM

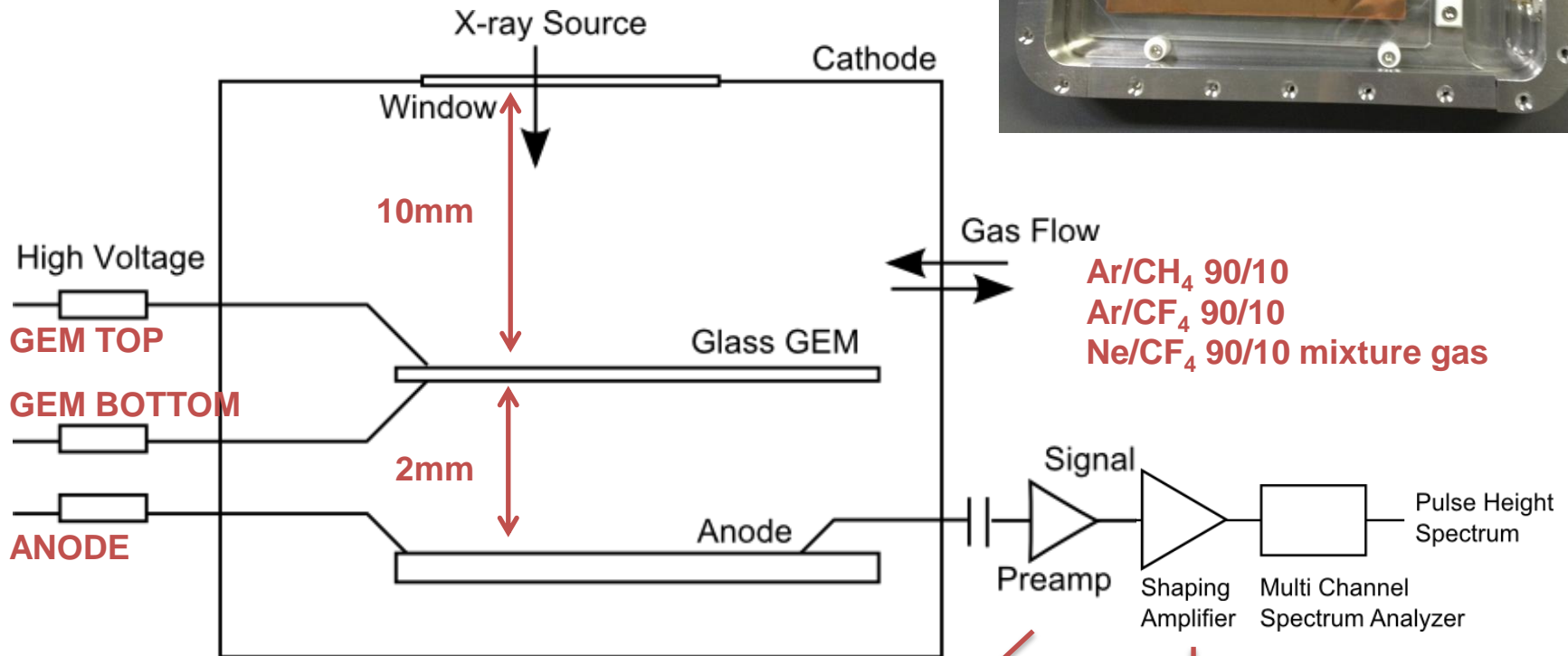
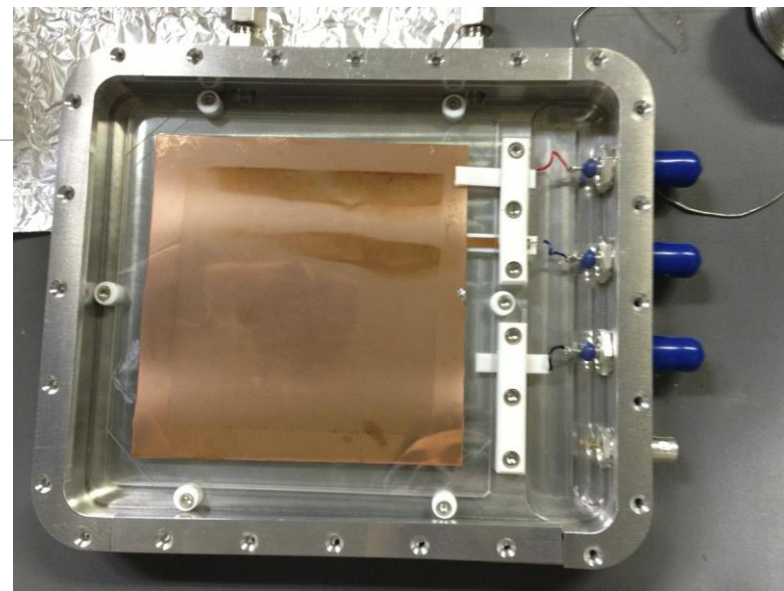
## No Outgas

- ▶ No outgas from the substrate  
(since it is inorganic material)

## Fabricating Process

- ▶ Direct etching -> good uniformity
- ▶ Easy to fabricate

# Setup



High Voltage

GEM TOP

GEM BOTTOM

ANODE

X-ray Source

Window  
10mm

Cathode

2mm

Glass GEM

Anode

Gas Flow

Ar/CH<sub>4</sub> 90/10

Ar/CF<sub>4</sub> 90/10

Ne/CF<sub>4</sub> 90/10 mixture gas

Signal

Preamp

Shaping  
Amplifier

Multi Channel  
Spectrum Analyzer

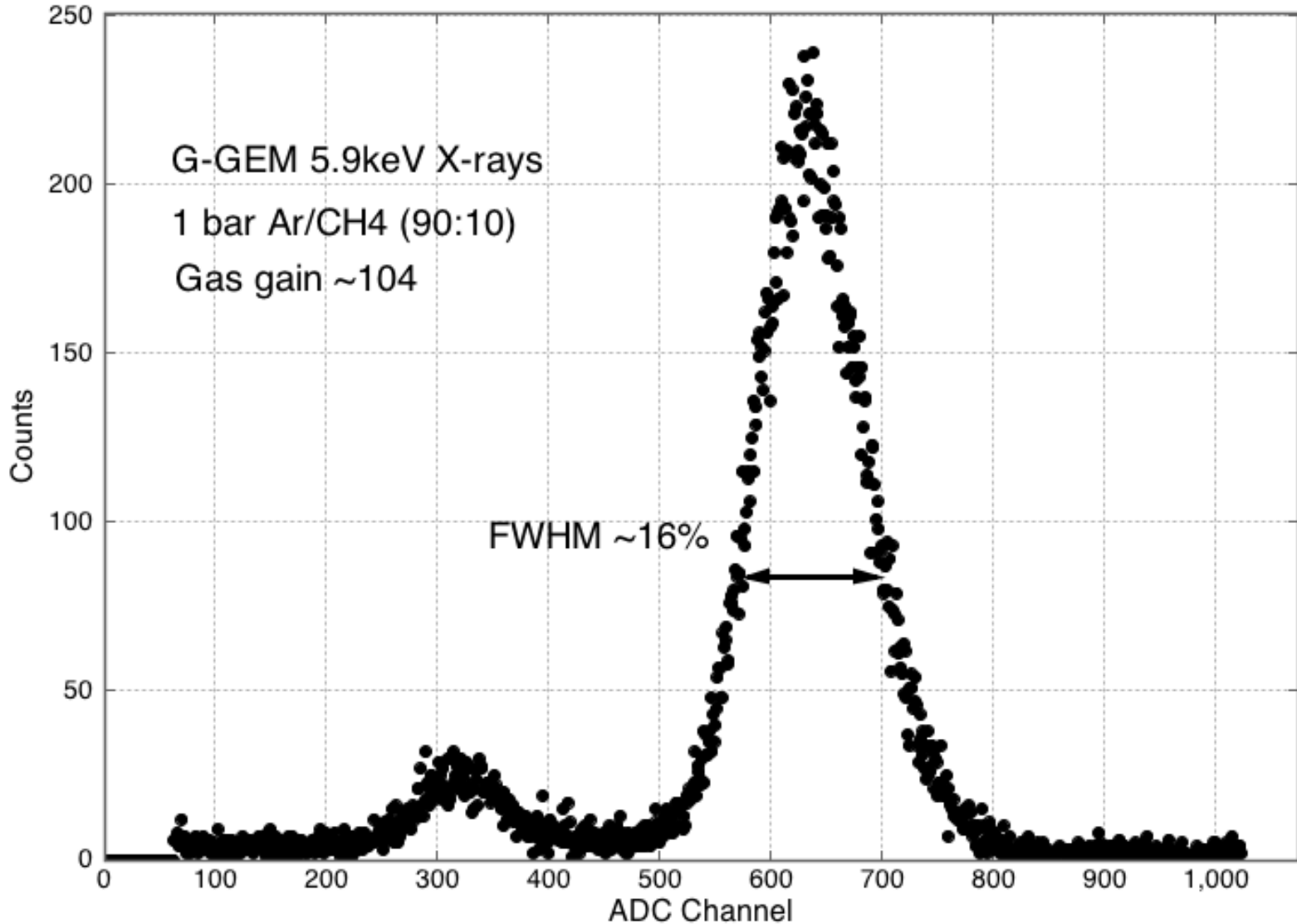
Pulse Height  
Spectrum

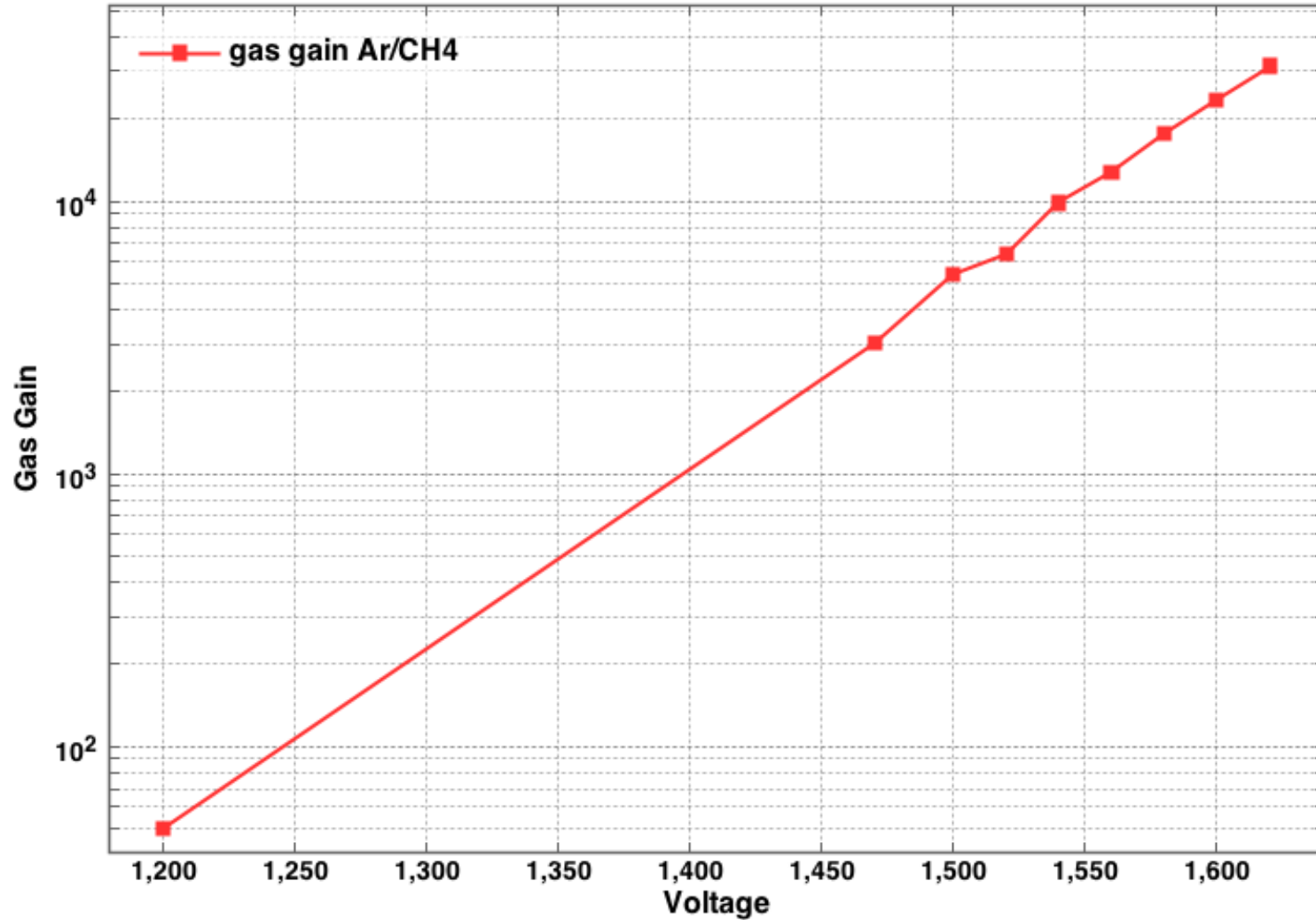
Ortec 710  
Ortec 660

Preamp (1V/pC)

Shaping Amplifier (Type:CP4419)  
Time Const : 0.5usec  
Gain : x1

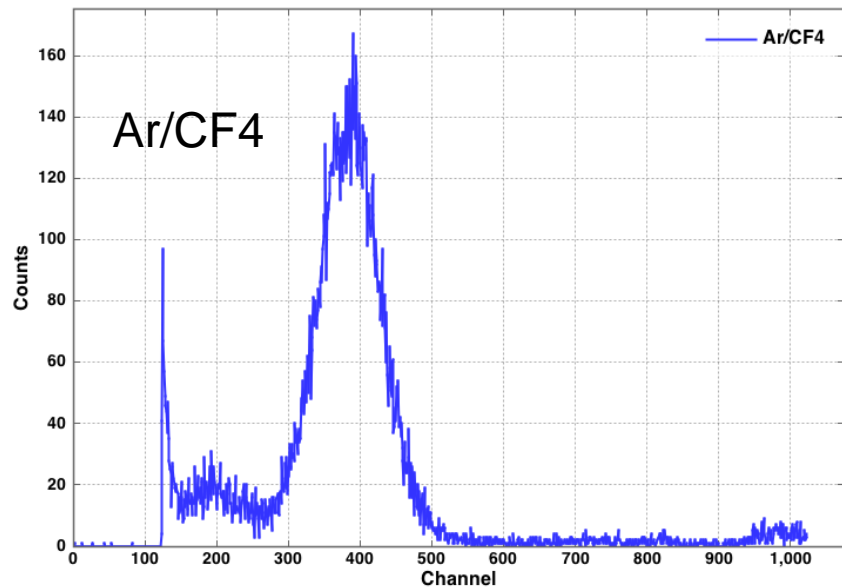
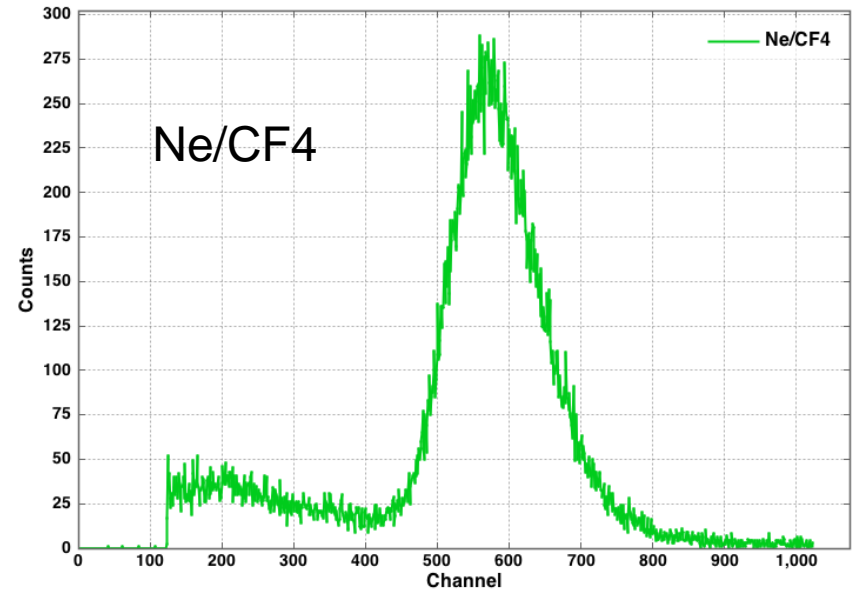
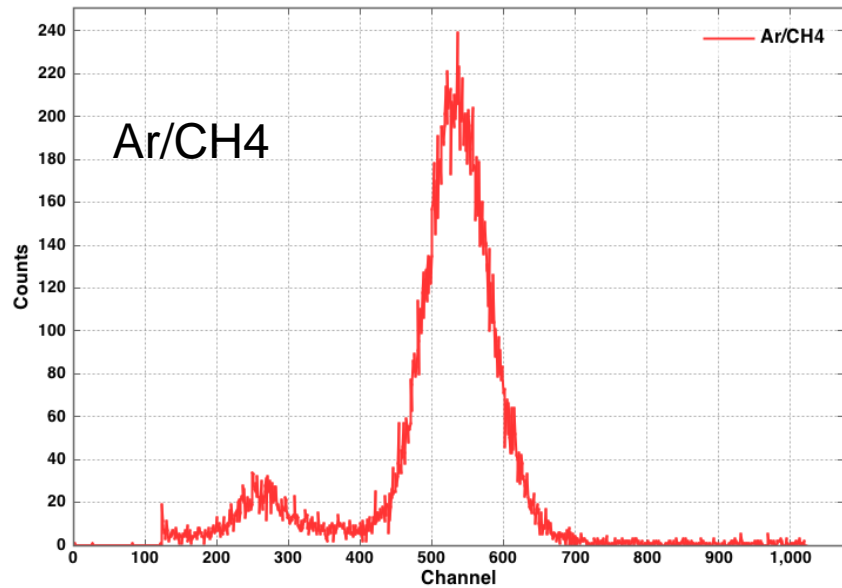
Takeshi Fujiwara



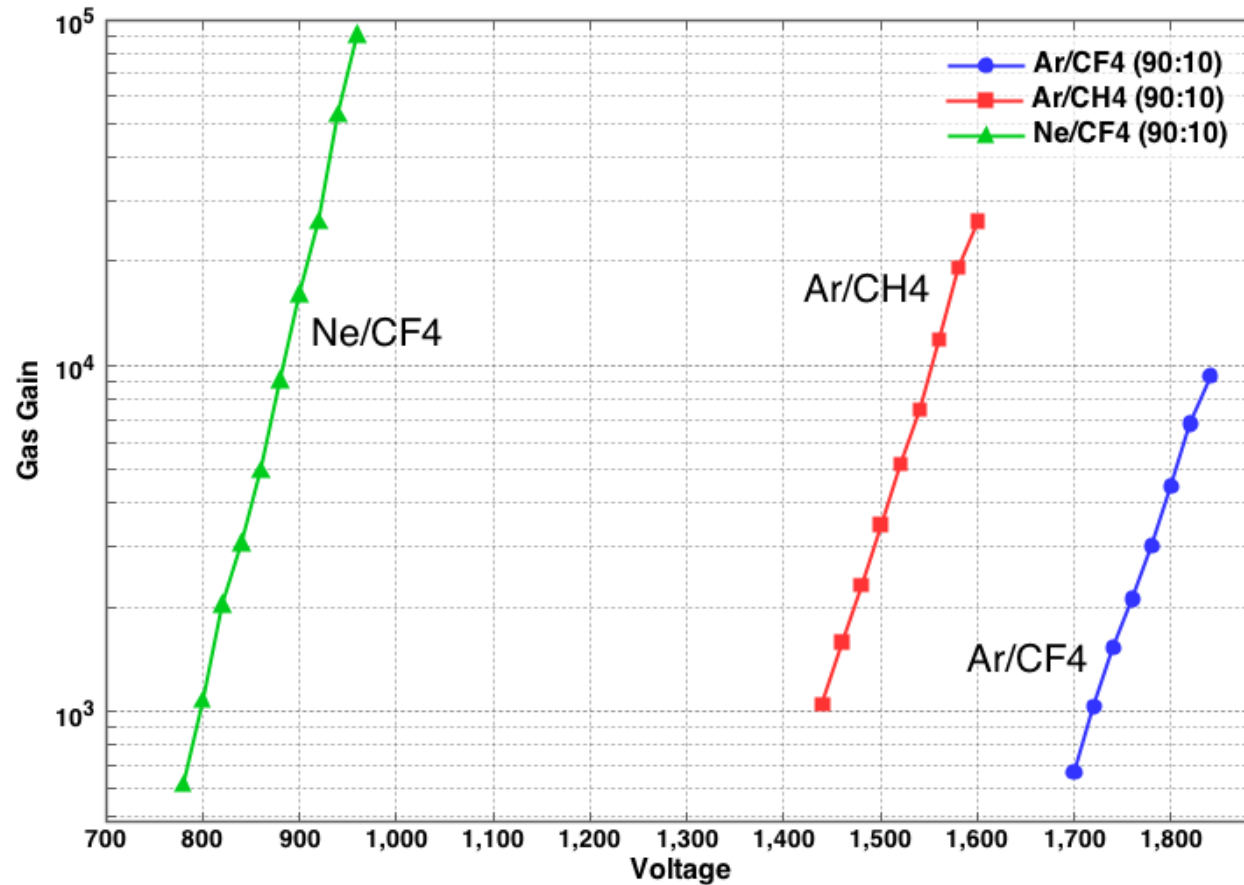


[GlassGEM] Thickness: 680 $\mu$ m, Hole diameter: 170 $\mu$ m

# Energy spectrum in various gas ( $^{55}\text{Fe}$ 5.9 keV X-ray source)

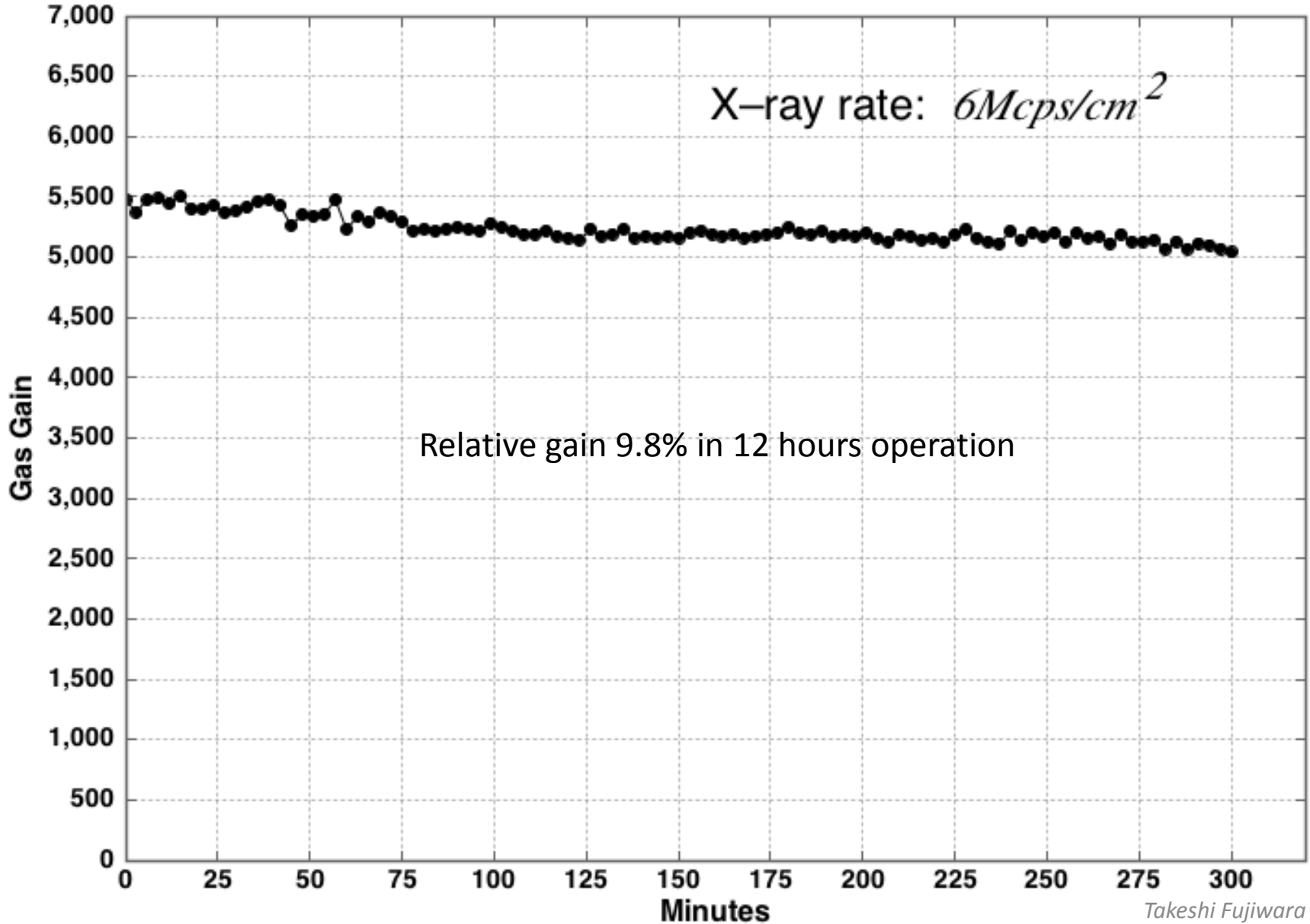


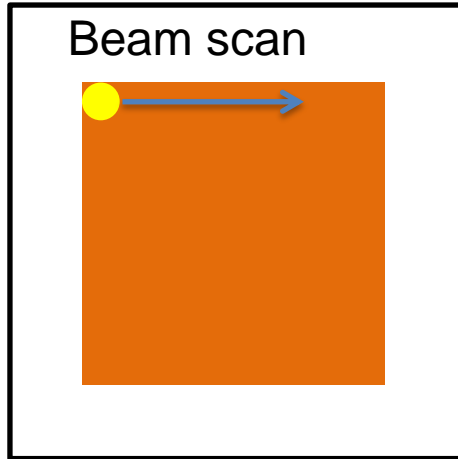
- ▶ Operated in Ar/CH4, Ar/CF4, Ne/CF4 gas mixture
- ▶ Ar/CH4 (90:10) gain 10,000
- ▶ Ne/CF4 (90:10) gain 10,000
- ▶ Ar/CF4 (90:10) gain 5,000



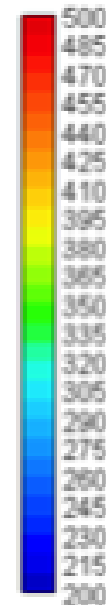
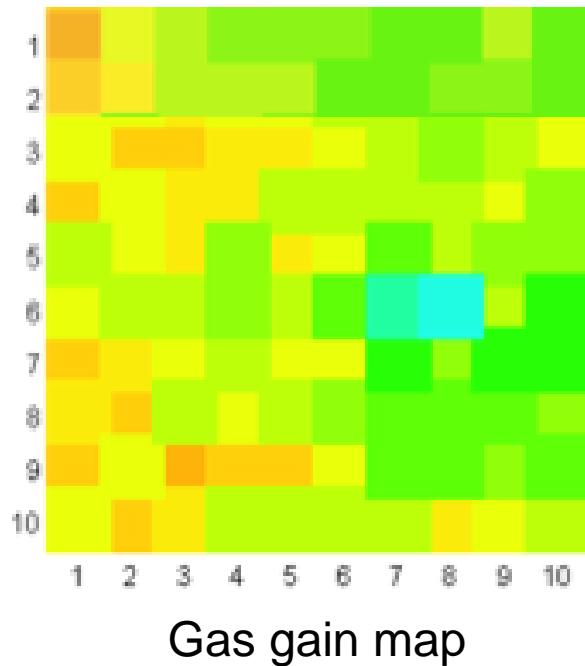
- ▶ Maximum gas gain
  - ▷  $9.8 \times 10^4$  @ Ne/CF4 (90:10)
  - ▷  $3.2 \times 10^4$  @ Ar/CH4 (90:10)
  - ▷  $9.5 \times 10^3$  @ Ar/CF4 (90:10)

# Gas gain stability (1 bar Pr10)





- ▶ Tested at KEK PF (synchrotron radiation facility)
- ▶ 6keV 0.2mm $\Phi$  collimated beam
- ▶ 700kHz/cm<sup>2</sup>
- ▶ Beam scan 10 \* 10

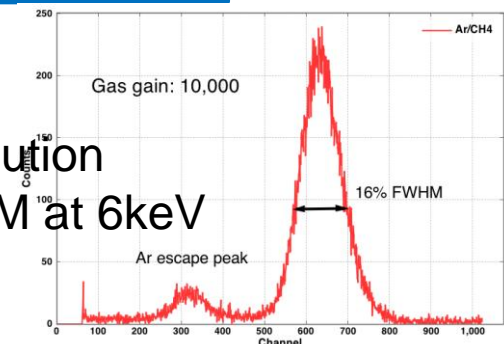


## Varies of gas gain

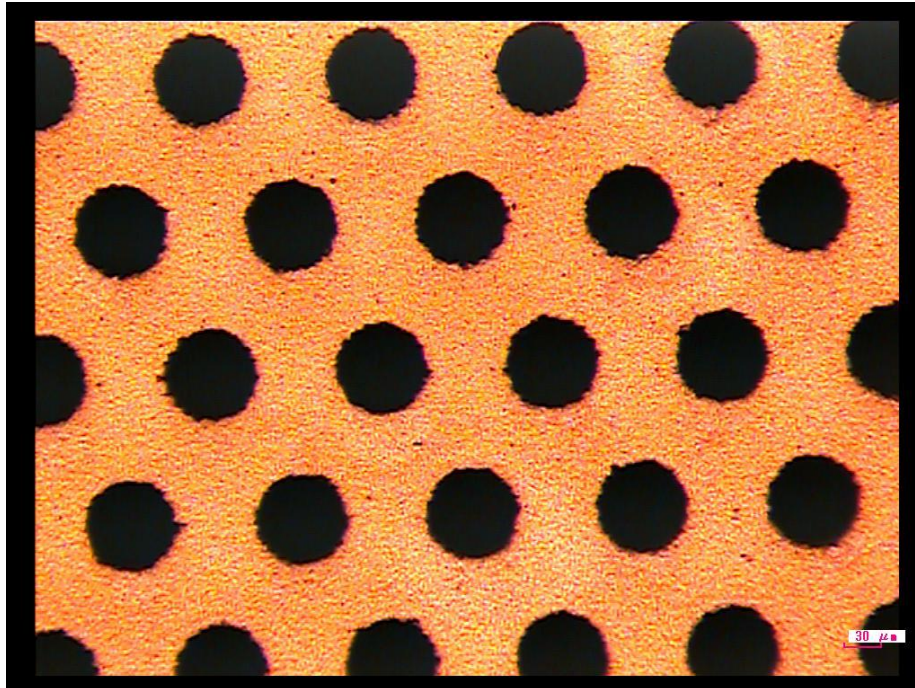
Entire area

Gas gain  
min. 9987  
max 12306

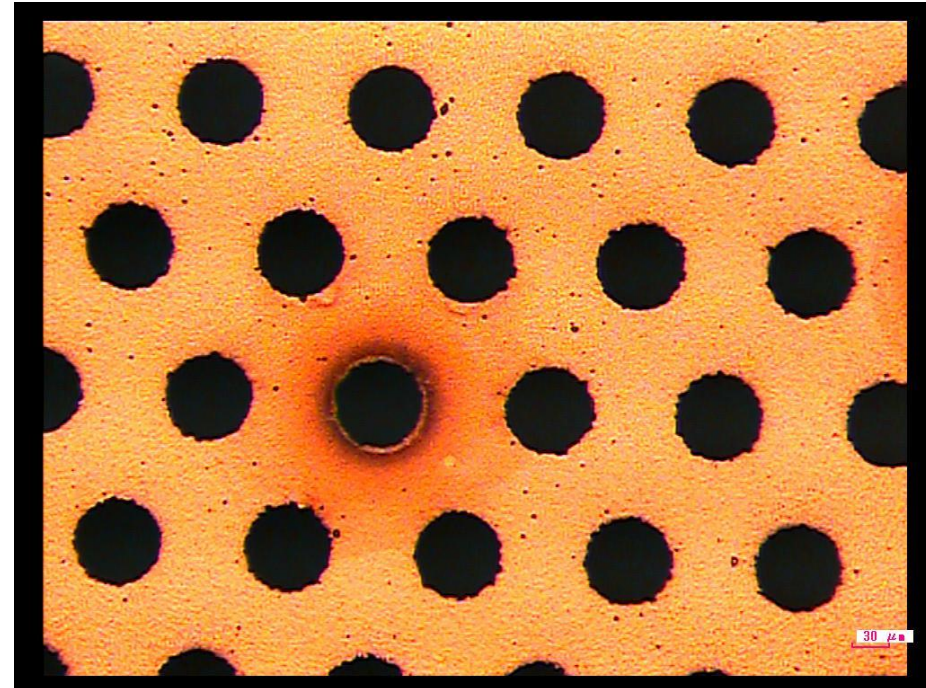
Energy resolution  
15.8% FWHM at 6keV







*Before operation*



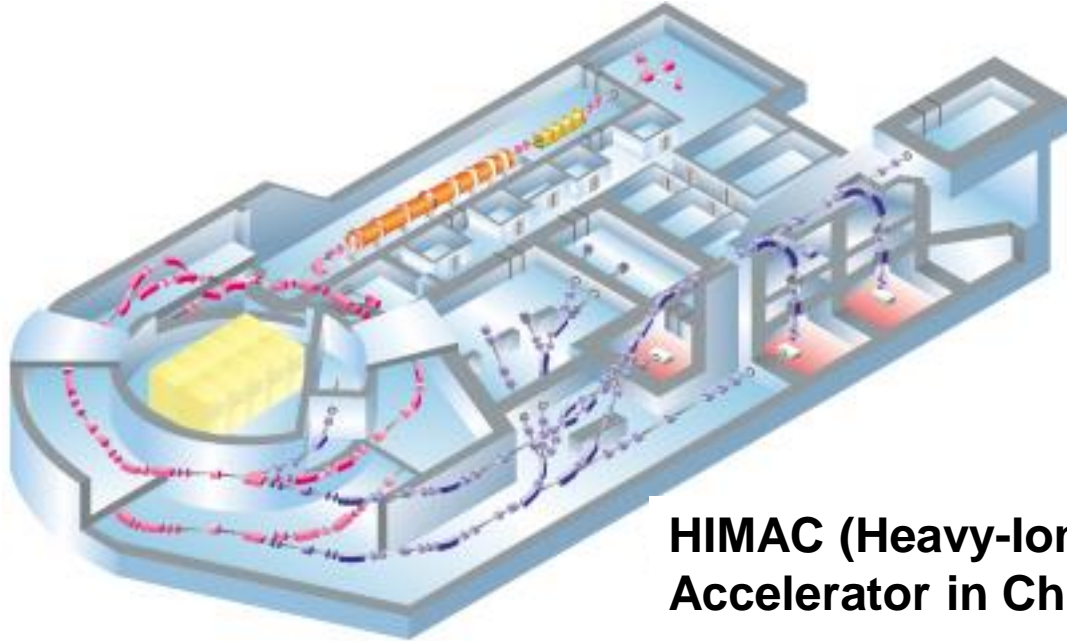
*Discharged part of GlassGEM*

- During the operation, several sparks were observed (heard) but nothing to do with the Glass GEM.
- Some burned print was observed around the hole, but no change of gas gain and energy resolution.
- **Glass substrate has a tolerance against sparks.**

# GlassGEM for medical application

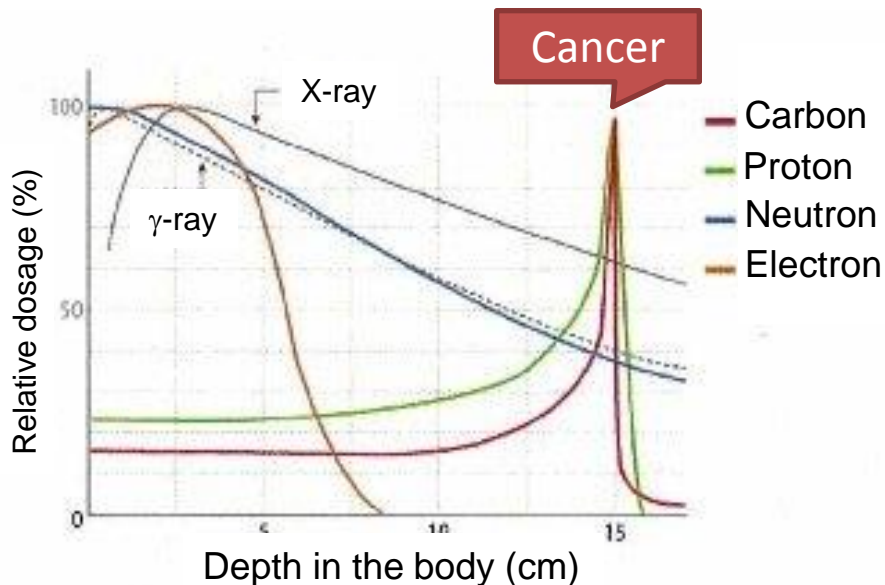
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2-D Carbon Ion Beam Dosimeter



- 290 MeV Carbon ion accelerator for cancer therapy
- Localize the radiation dosage precisely using Bragg peak.
- 2-D dosimeter is required for accurate treatment planning.

**HIMAC (Heavy-Ion Medical Accelerator in Chiba)**

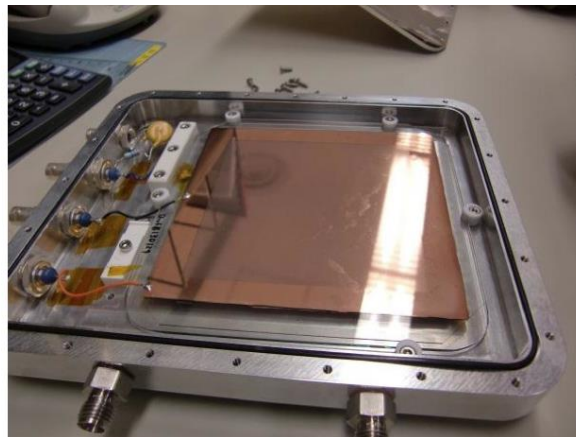
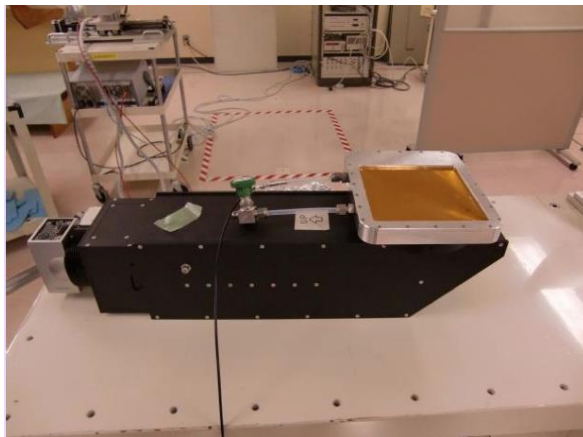
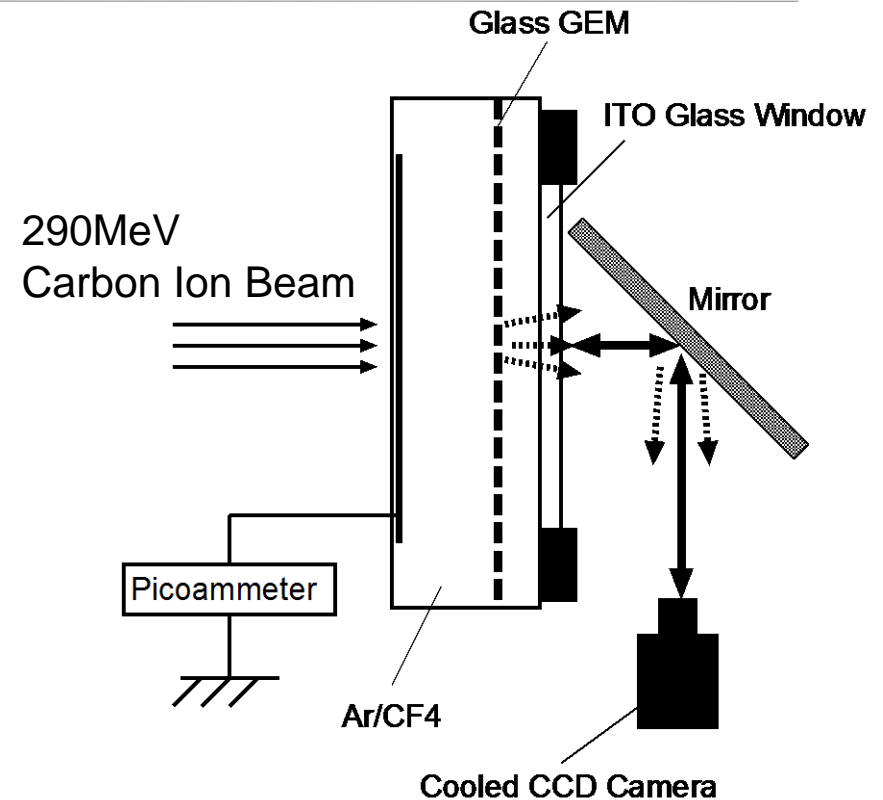


## ▶ Beam

- ▶ 290MeV Carbon Ion Beam
- ▶ 10cm $\Phi$

## ▶ Detector

- ▶ GlassGEM + ITO Anode
- ▶ Ar/CF<sub>4</sub> for scintillation gas
- ▶ Cooled CCD for imager
- ▶ Mirror to avoid irradiation to CCD



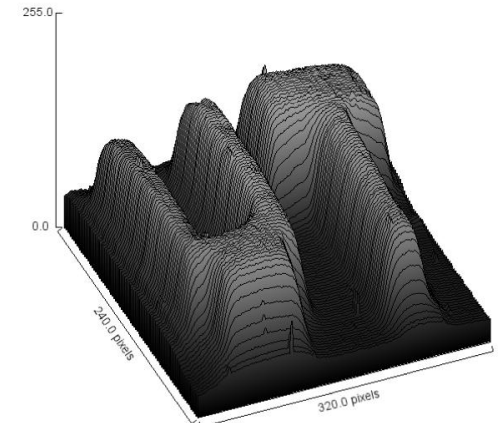
## ▶ “UT” (University of Tokyo)



Collimator

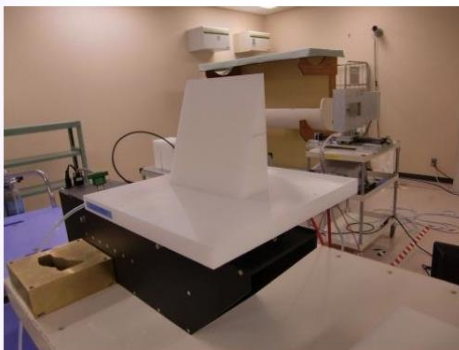


Obtained Image

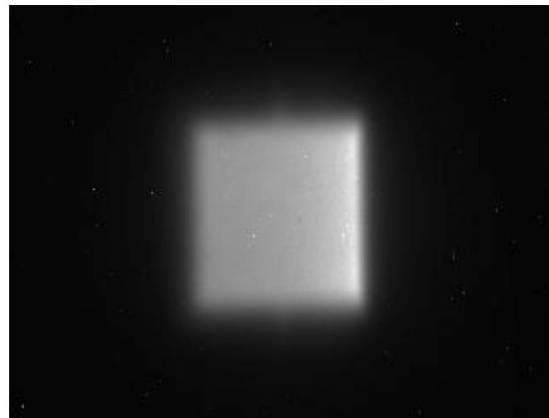


Dosage map

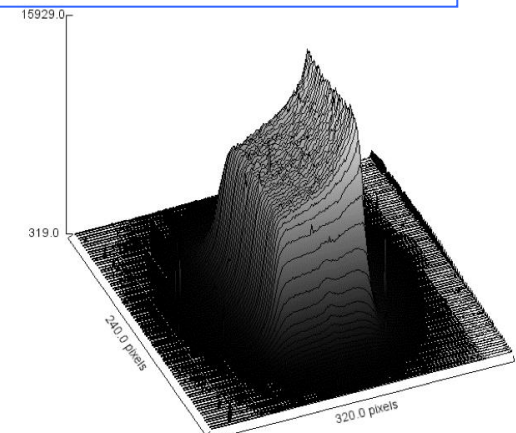
## ▶ Bragg peak measurement



Moderator on GEM

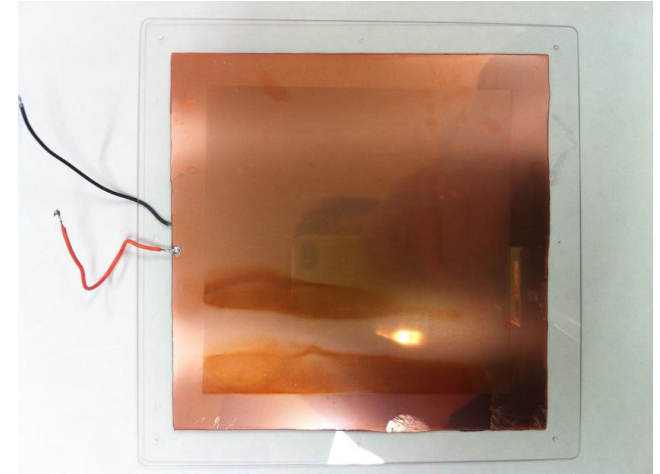


Obtained Image



Dosage map

- ▶ Succeed in fabricating GEM with new material
  - ▷ **photo etchable glass**
- ▶ Fabricated with **PEG3 substrate** (HOYA corp.)
- ▶ Effective size: 100 \* 100mm<sup>2</sup>
- ▶ High gain with single substrate
  - ▷ Gas gain :  $3 \times 10^4$  @Ar/CH<sub>4</sub> (90:10, 1bar)
  - ▷ Gas gain :  $9 \times 10^4$  @Ne/CF<sub>4</sub> (90:10, 1bar)
- ▶ Energy resolution: 15 to 18%
- ▶ Glass GEM is a **outgas free** material : suitable for sealed gas application  
ex. He-3 neutron detector



Thank you for your attention.